

Gon-Ho Kim

List of Publications by Citations

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The third column is the impact factor (IF) of the journal, and the fourth column is the number of citations of the article.

83

papers

622

citations

12

h-index

20

g-index

101

ext. papers

725

ext. citations

2.3

avg, IF

3.52

L-index

#	Paper	IF	Citations
83	Polymer surface modification by plasma source ion implantation. <i>Surface and Coatings Technology</i> , 1997 , 93, 261-264	4.4	109
82	Global model analysis of negative ion generation in low-pressure inductively coupled hydrogen plasmas with bi-Maxwellian electron energy distributions. <i>Physics of Plasmas</i> , 2015 , 22, 033506	2.1	29
81	Effect on plasma and etch-rate uniformity of controlled phase shift between rf voltages applied to powered electrodes in a triode capacitively coupled plasma reactor. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2009 , 27, 13-19	2.9	28
80	Efficacy of a new navigable percutaneous disc decompression device (LDISQ) in patients with herniated nucleus pulposus related to radicular pain. <i>Pain Medicine</i> , 2011 , 12, 370-6	2.8	24
79	Influence of H ⁺ ion irradiation on the surface and microstructural changes of a nuclear graphite. <i>Fusion Engineering and Design</i> , 2012 , 87, 344-351	1.7	23
78	Fabrication of sintered tungsten by spark plasma sintering and investigation of thermal stability. <i>International Journal of Refractory Metals and Hard Materials</i> , 2017 , 69, 164-169	4.1	20
77	. <i>IEEE Transactions on Semiconductor Manufacturing</i> , 2015 , 28, 241-246	2.6	20
76	Development of the Virtual Metrology for the Nitride Thickness in Multi-Layer Plasma-Enhanced Chemical Vapor Deposition Using Plasma-Information Variables. <i>IEEE Transactions on Semiconductor Manufacturing</i> , 2018 , 31, 232-241	2.6	18
75	Plasma uniformity and phase-controlled etching in a very high frequency capacitive discharge. <i>Journal of Applied Physics</i> , 2009 , 106, 023303	2.5	15
74	Characteristics of a non-Maxwellian electron energy distribution in a low-pressure argon plasma. <i>Journal of the Korean Physical Society</i> , 2014 , 64, 1819-1827	0.6	13
73	Quantitation of the ROS production in plasma and radiation treatments of biotargets. <i>Scientific Reports</i> , 2019 , 9, 19837	4.9	13
72	High-temperature thermo-mechanical behavior of functionally graded materials produced by plasma sprayed coating: Experimental and modeling results. <i>Metals and Materials International</i> , 2016 , 22, 817-824	2.4	12
71	Effect of annealing with pressure on tungsten film properties fabricated by atmospheric plasma spray. <i>Metals and Materials International</i> , 2014 , 20, 1037-1042	2.4	12
70	Frequency and electrode shape effects on etch rate uniformity in a dual-frequency capacitive reactor. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2012 , 30, 061301	2.9	12
69	Effects of shroud gas injection on material properties of tungsten layers coated by plasma spraying. <i>Thin Solid Films</i> , 2010 , 518, 6369-6372	2.2	12
68	Improvement of mechanical property of air plasma sprayed tungsten film using pulsed electric current treatment. <i>International Journal of Refractory Metals and Hard Materials</i> , 2016 , 60, 99-103	4.1	11
67	Deposition/erosion and H/D retention characteristics in gaps of PFCs in KSTAR studied by cavity technique. <i>Journal of Nuclear Materials</i> , 2013 , 438, S698-S706	3.3	11

66	The measurement of nitrogen ion species ratio in inductively coupled plasma source ion implantation. <i>Surface and Coatings Technology</i> , 2001 , 136, 106-110	4.4	10
65	The bactericidal effect of an atmospheric-pressure plasma jet on biofilms on sandblasted and acid-etched titanium discs. <i>Journal of Periodontal and Implant Science</i> , 2019 , 49, 319-329	2	10
64	Determination of electron energy probability function in low-temperature plasmas from current-voltage characteristics of two Langmuir probes filtered by Savitzky-Golay and Blackman window methods. <i>Current Applied Physics</i> , 2015 , 15, 1173-1183	2.6	9
63	Field-emission performance and structural change mechanism of multiwalled carbon nanotubes by oxygen plasma treatment. <i>Thin Solid Films</i> , 2013 , 547, 202-206	2.2	9
62	Effects of metastable species in helium and argon atmospheric pressure plasma jets (APPJs) on inactivation of periodontopathogenic bacteria. <i>Journal of the Korean Physical Society</i> , 2016 , 68, 1176-1191	0.6	8
61	Measurement of sheath expansion in plasma source ion implantation. <i>Surface and Coatings Technology</i> , 2001 , 136, 97-101	4.4	8
60	Design of optical emission spectroscopy based plasma parameter controller for real-time advanced equipment control. <i>Computers and Chemical Engineering</i> , 2017 , 100, 38-47	4	7
59	Preliminary test results on tungsten tile with castellation structures in KSTAR. <i>Fusion Engineering and Design</i> , 2014 , 89, 1704-1708	1.7	7
58	Enhancement of deuterium retention in damaged tungsten by plasma-induced defect clustering. <i>Nuclear Fusion</i> , 2017 , 57, 126042	3.3	7
57	Recrystallization of bulk and plasma-coated tungsten with accumulated thermal energy relevant to Type-I ELM in ITER H-mode operation. <i>Journal of Nuclear Materials</i> , 2015 , 463, 215-218	3.3	7
56	Characteristics of vapor coverage formation on an RF-driven metal electrode to discharge a plasma in saline solution. <i>Plasma Sources Science and Technology</i> , 2012 , 21, 055017	3.5	7
55	Effects of argon and oxygen flow rate on water vapor barrier properties of silicon oxide coatings deposited on polyethylene terephthalate by plasma enhanced chemical vapor deposition. <i>Thin Solid Films</i> , 2010 , 518, 1929-1934	2.2	7
54	Metal surface oxidation by using dielectric barrier discharge. <i>Thin Solid Films</i> , 2010 , 518, 6394-6398	2.2	7
53	Mechanism of cone-shaped carbon nanotube bundle formation by plasma treatment. <i>Carbon</i> , 2010 , 48, 3864-3873	10.4	7
52	Etching of Multi-Walled Carbon Nanotubes Using Energetic Plasma Ions. <i>Japanese Journal of Applied Physics</i> , 2006 , 45, 8317-8322	1.4	7
51	Deuterium ion irradiation induced blister formation and destruction. <i>Fusion Engineering and Design</i> , 2016 , 109-111, 624-628	1.7	6
50	Standing wave effect on plasma distribution in an inductively coupled plasma source with a short antenna. <i>Journal Physics D: Applied Physics</i> , 2014 , 47, 015205	3	6
49	Hydroxyl Radical Generation on Bubble Surface of Aqua-Plasma Discharge. <i>IEEE Transactions on Plasma Science</i> , 2011 , 39, 2658-2659	1.3	6

48	Development of Virtual Metrology Using Plasma Information Variables to Predict Si Etch Profile Processed by SF/O/Ar Capacitively Coupled Plasma. <i>Materials</i> , 2021 , 14,	3.5	6
47	Ion-neutral collision effect on ion-ion two-stream-instability near sheath-presheath boundary in two-ion-species plasmas. <i>Plasma Sources Science and Technology</i> , 2017 , 26, 06LT01	3.5	5
46	Bullet Velocity Distribution of a Helium Atmospheric-Pressure Plasma Jet in Various N ₂ /O ₂ Mixed Ambient Conditions. <i>IEEE Transactions on Plasma Science</i> , 2015 , 43, 2054-2063	1.3	5
45	Numerical investigation of plasma recovery in plasma source ion implantation. <i>Thin Solid Films</i> , 2012 , 521, 197-200	2.2	5
44	Field emission characteristics of cone-shaped carbon-nanotube bundles fabricated using an oxygen plasma. <i>Journal of the Korean Physical Society</i> , 2012 , 61, 1083-1087	0.6	5
43	Dynamic sheath expansion in a non-uniform plasma with ion drift. <i>Plasma Sources Science and Technology</i> , 2011 , 20, 045014	3.5	5
42	Measurement of expanding plasma sheath from a target biased by a negative pulse with a fast rise time. <i>Journal of Applied Physics</i> , 2003 , 93, 1384-1388	2.5	5
41	Vacuum pump age effects by the exposure to the corrosive gases on the Cr etch rate as observed using optical emission spectroscopy in an Ar/O ₂ /Cl ₂ mixed plasma. <i>Thin Solid Films</i> , 2016 , 603, 154-159	2.2	5
40	Application of PI-VM for management of the metal target plasma etching processes in OLED display manufacturing. <i>Plasma Physics and Controlled Fusion</i> , 2019 , 61, 014032	2	5
39	Driving frequency dependency of gas species in the bubble formation for aqua-plasma generation. <i>Current Applied Physics</i> , 2013 , 13, S54-S58	2.6	4
38	Design of a self-tuning adaptive model predictive controller using recursive model parameter estimation for real-time plasma variable control. <i>Computers and Chemical Engineering</i> , 2019 , 123, 126-142	4	4
37	Characteristics of a plasma information variable in phenomenology-based, statistically-tuned virtual metrology to predict silicon dioxide etching depth. <i>Current Applied Physics</i> , 2019 , 19, 1068-1075	2.6	3
36	How to determine the relative ion concentrations of multiple-ion-species plasmas generated in the multi-dipole filament source. <i>Journal Physics D: Applied Physics</i> , 2015 , 48, 225201	3	3
35	Investigation of SOL plasma interaction with graphite PFC. <i>Journal of Nuclear Materials</i> , 2015 , 463, 753-756	3.5	3
34	Numerical Analysis on the Electrical and Thermal Flow Characteristics of Ar-N ₂ Inductively Coupled Plasma Torch System. <i>Journal of the Korean Physical Society</i> , 2018 , 72, 755-764	0.6	3
33	Cause analysis of the faults in HARC etching processes by using the PI-VM model for OLED display manufacturing. <i>Plasma Processes and Polymers</i> , 2019 , 16, 1900030	3.4	3
32	Low-energy D ⁺ and H ⁺ ion irradiation effects on highly oriented pyrolytic graphite. <i>Journal of Applied Physics</i> , 2013 , 114, 214310	2.5	3
31	Time-resolved plasma measurement in a high-power pulsed ICP source for large area. <i>Surface and Coatings Technology</i> , 2004 , 186, 161-164	4.4	3

30	Predictive control of the plasma processes in the OLED display mass production referring to the discontinuity qualifying PI-VM. <i>Physics of Plasmas</i> , 2020 , 27, 083507	2.1	3
29	Experimental investigation of plasma recovery during the pulse-off time in plasma source ion implantation. <i>Thin Solid Films</i> , 2013 , 547, 13-16	2.2	2
28	Characterization of Two Radio-Frequency Driven Dual Antenna Negative Hydrogen Ion Sources. <i>Fusion Science and Technology</i> , 2015 , 68, 105-112	1.1	2
27	Hydrogen Adsorption Property of Pore Structure Controlled Single-Walled Carbon Nanotubes with Electron Irradiation. <i>Journal of Physical Chemistry C</i> , 2010 , 114, 13975-13978	3.8	2
26	Self-consistent circuit model for plasma source ion implantation. <i>Review of Scientific Instruments</i> , 2008 , 79, 02C502	1.7	2
25	Investigation of Current on the Conducting Target Biased with a Large Negative Potential in the Non-Uniform Plasma. <i>Japanese Journal of Applied Physics</i> , 2006 , 45, L686-L689	1.4	2
24	The effect of plasma exposure and annealing atmosphere on shallow junction formation using plasma source ion implantation. <i>Surface and Coatings Technology</i> , 2002 , 157, 19-25	4.4	2
23	Observation of oversaturation-induced defect formation in tungsten irradiated by low energy deuterium ion. <i>Journal of the Korean Physical Society</i> , 2016 , 69, 518-524	0.6	2
22	Optimal Parameters for Intervertebral Disk Resection Using Aqua-Plasma Beams. <i>Journal of Neurological Surgery, Part A: Central European Neurosurgery</i> , 2019 , 80, 34-38	1.1	2
21	Plasma information-based virtual metrology (PI-VM) and mass production process control. <i>Journal of the Korean Physical Society</i> , 1	0.6	2
20	Optical diagnostics for the highly populated tail of an electron energy distribution function in very-high-frequency capacitively coupled plasma using spin- and dipole-forbidden lines. <i>Journal Physics D: Applied Physics</i> , 2017 , 50, 225201	3	1
19	Characteristics of OH* Generation in Pin-to-Electrolyte Discharges. <i>IEEE Transactions on Plasma Science</i> , 2014 , 42, 2814-2815	1.3	1
18	Effect of Helmholtz Oscillation on Auto-shroud for APS Tungsten Carbide Coating. <i>Journal of Thermal Spray Technology</i> , 2013 , 22, 756-763	2.5	1
17	Analysis of Langmuir probe data using wavelet transform. <i>IEEE Transactions on Plasma Science</i> , 2004 , 32, 355-361	1.3	1
16	Design and operation of an Omegatron mass spectrometer for measurements of positive and negative ion species in electron cyclotron resonance plasmas. <i>Plasma Sources Science and Technology</i> , 2000 , 9, 97-107	3.5	1
15	Safety evaluation of atmospheric pressure plasma jets in and experiments. <i>Journal of Periodontal and Implant Science</i> , 2021 , 51, 213-223	2	1
14	Development of model predictive control of fluorine density in SF ₆ /O ₂ /Ar etch plasma by oxygen flow rate. <i>Current Applied Physics</i> , 2022 , 36, 183-186	2.6	1
13	Determination of electron energy distribution function shape for non-Maxwellian plasmas using floating harmonics method. <i>Journal Physics D: Applied Physics</i> , 2015 , 48, 022001	3	0

12	Population Kinetics Modeling of Low-Temperature Argon Plasma. <i>Atoms</i> , 2021 , 9, 100	2.1	0
11	Micro-range uniformity control of the etching profile in the OLED display mass production referring to the PI-VM model. <i>Physics of Plasmas</i> , 2021 , 28, 103505	2.1	0
10	Recursive Model Estimation for the Plasma Parameters Quality Control. <i>Computer Aided Chemical Engineering</i> , 2018 , 43, 279-284	0.6	
9	Analysis on Interface Diffusion-Induced Embrittlement between Tungsten and Graphite with Reactive Diffusion Barrier Model. <i>Fusion Science and Technology</i> , 2015 , 68, 113-119	1.1	
8	Laser-Assisted H _β Spectroscopy for Measurement of Negative Ion Density in a Hydrogen Plasma. <i>Fusion Science and Technology</i> , 2015 , 68, 171-177	1.1	
7	. <i>IEEE Transactions on Plasma Science</i> , 2009 , 37, 773-784	1.3	
6	Calculation of transport parameters in KT-1 tokamak edge plasma. <i>Current Applied Physics</i> , 2001 , 1, 497-503		
5	Phenomenology-based model predictive control of electron density in Ar/SF ₆ capacitively coupled etch plasma. <i>Journal of the Korean Physical Society</i> , 2022 , 80, 233-240	0.6	
4	Sparse Bayesian long short-term memory networks for computationally efficient stochastic modeling of plasma etch processes. <i>Computers and Chemical Engineering</i> , 2022 , 159, 107696	4	
3	Development of plasma sources and diagnostics for the simulation of fusion edge plasmas. <i>Journal of the Korean Physical Society</i> , 1	0.6	
2	Online System Identification for the Real Time Control of the Plasma Parameters. <i>Computer Aided Chemical Engineering</i> , 2018 , 2041-2046	0.6	
1	Simulations of fusion edge plasmas by linear plasma devices: physics and plasma-material interactions. <i>Journal of the Korean Physical Society</i> , 1	0.6	